EE 330 Lecture 16

Devices in Semiconductor Processes

- Diodes (continued)
- Capacitors
- MOSFETs

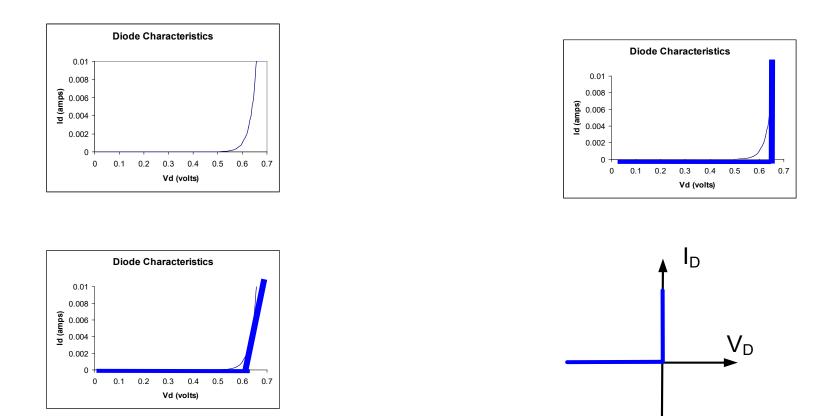
Spring 2024 Exam Schedule

- Exam 1 Friday Feb 16
- Exam 2 Friday March 8
- Exam 3 Friday April 19

Final Exam Tuesday May 7 7:30 AM - 9:30 AM

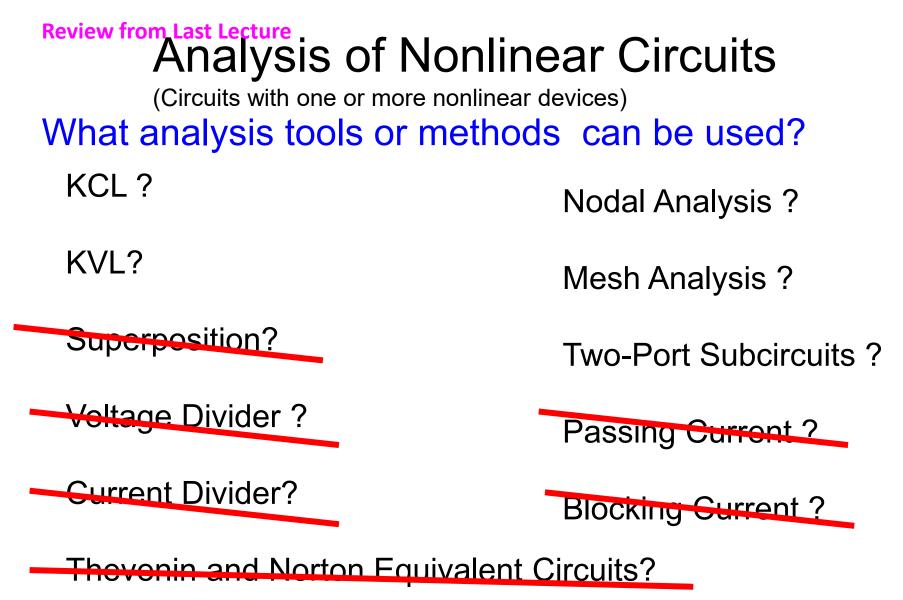
Review from Last Lecture

Diode Models



Which model should be used?

The simplest model that will give acceptable results in the analysis of a circuit



- How are piecewise models accommodated?
- Will address the issue of how to rigorously analyze nonlinear circuits with piecewise models later

Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

Process:

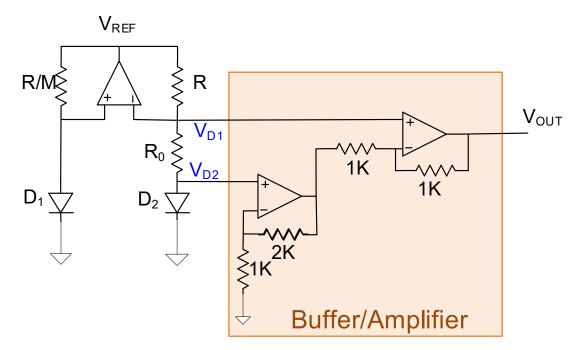
- 1. Guess state of the device
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify model (if necessary)

Observations:

- o Analysis generally simplified dramatically (particularly if piecewise model is linear)
- Approach applicable to wide variety of nonlinear devices
- $\circ~$ Closed-form solutions give insight into performance of circuit
- $\circ~$ Usually much faster than solving the nonlinear circuit directly
- Wrong guesses in the state of the device do not compromise solution (verification will fail)
- \circ Helps to guess right the first time
- Detailed model is often not necessary with most nonlinear devices
- o Particularly useful if piecewise model is PWL (but not necessary)
- For <u>practical</u> circuits, the simplified approach usually applies

Key Concept For Analyzing Circuits with Nonlinear Devices

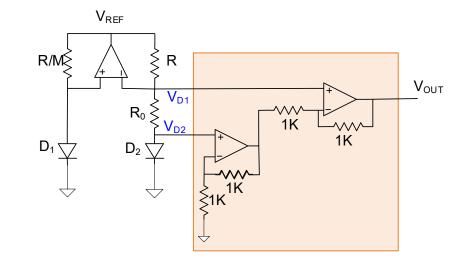
A Diode Application



If buffer/amplifier added, serves as temperature sensor at V_{OUT} $V_{OUT} = 2(V_{D1} - V_{D2})$ May need compensation and startup circuits

For appropriate R₀, serves as bandgap voltage reference (buffer/amplifier excluded) $V_{REF} = V_{D1} + \frac{R}{R_0} (V_{D1} - V_{D2})$

A Diode Application



$$V_{OUT} = 2 \left(V_{D1} - V_{D2} \right)$$

Analysis of temperature sensor (assume D_1 and D_2 matched)

$$I_{D2}(T) = \left(J_{SX}\left[T^{m}e^{\frac{-V_{os}}{V_{t}}}\right]\right)Ae^{\frac{V_{os}}{V_{t}}}$$

$$I_{D1}(T) = \left(J_{SX}\left[T^{m}e^{\frac{-V_{os}}{V_{t}}}\right]\right)Ae^{\frac{V_{os}}{V_{t}}}$$

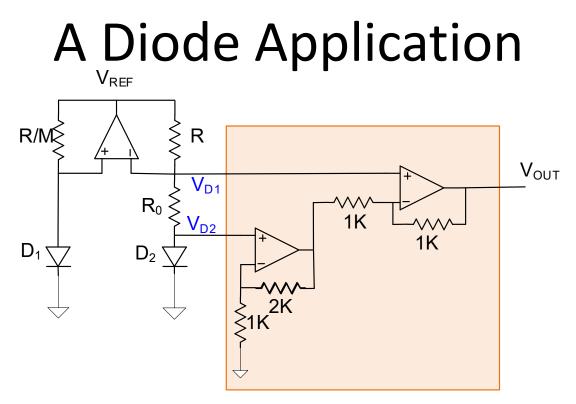
$$I_{D1}(T) = MI_{D2}(T)$$

$$V_{t} = \frac{k}{q}T$$

$$\left(J_{SX}\left[T^{m}e^{\frac{-V_{os}}{V_{t}}}\right]\right)Ae^{\frac{V_{os}}{V_{t}}}$$

$$Cancelling terms and taking ln we obtain
$$V_{D1} - V_{D2} = V_{t} In M$$
Thus
$$V_{OUT} = 2(V_{D1} - V_{D2}) = 2In M \bullet \frac{k}{q} T$$

$$T = V_{OUT} \frac{q}{2k ln M}$$$$



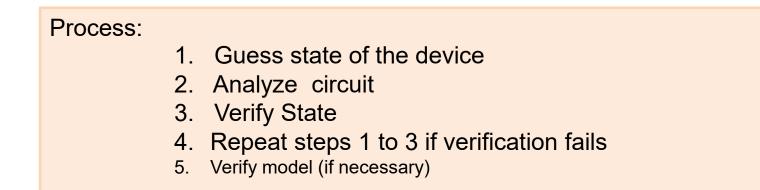
May need compensation and startup circuits

If buffer/amplifier added, serves as temperature sensor at V_{OUT}

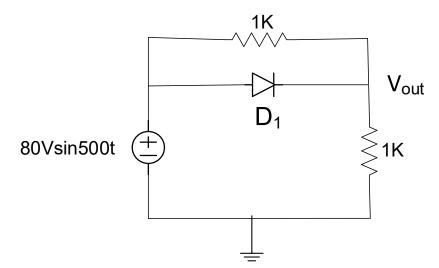
 $V_{OUT} = 2(V_{D1} - V_{D2}) \qquad \qquad T = V_{OUT} \frac{q}{2k \ln M}$ For appropriate R₀, serves as bandgap voltage reference $V_{REF} = V_{D1} + \frac{R}{R_0}(V_{D1} - V_{D2}) \qquad \qquad \ref{eq:result}$

Analysis of V_{REF} to show output is nearly independent of T and V_{DD} is more tedious

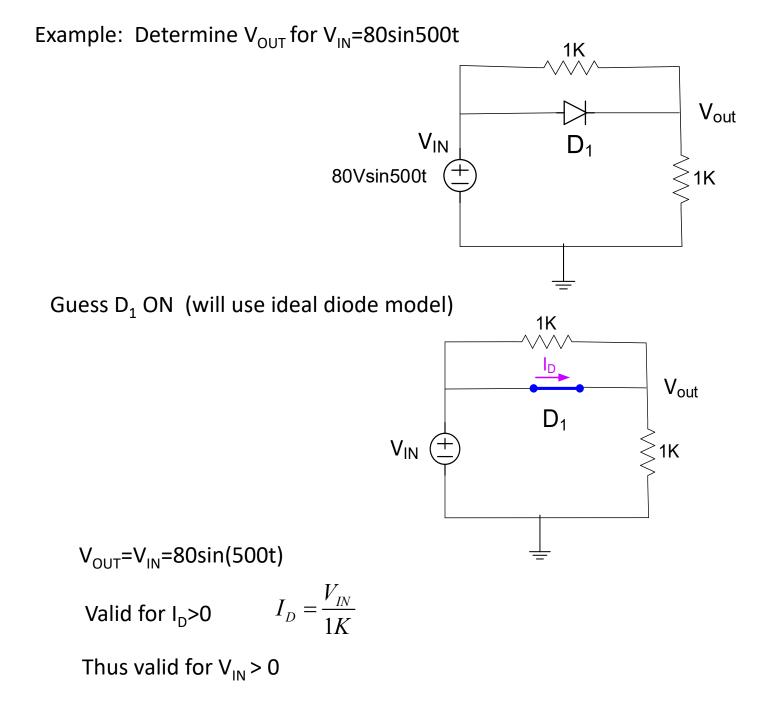
Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

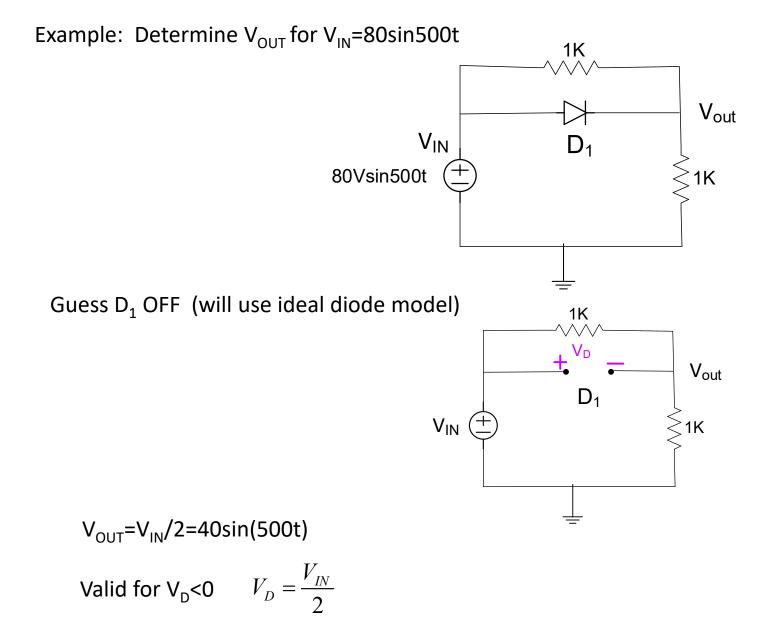


What about nonlinear circuits (using piecewise models) with time-varying inputs?



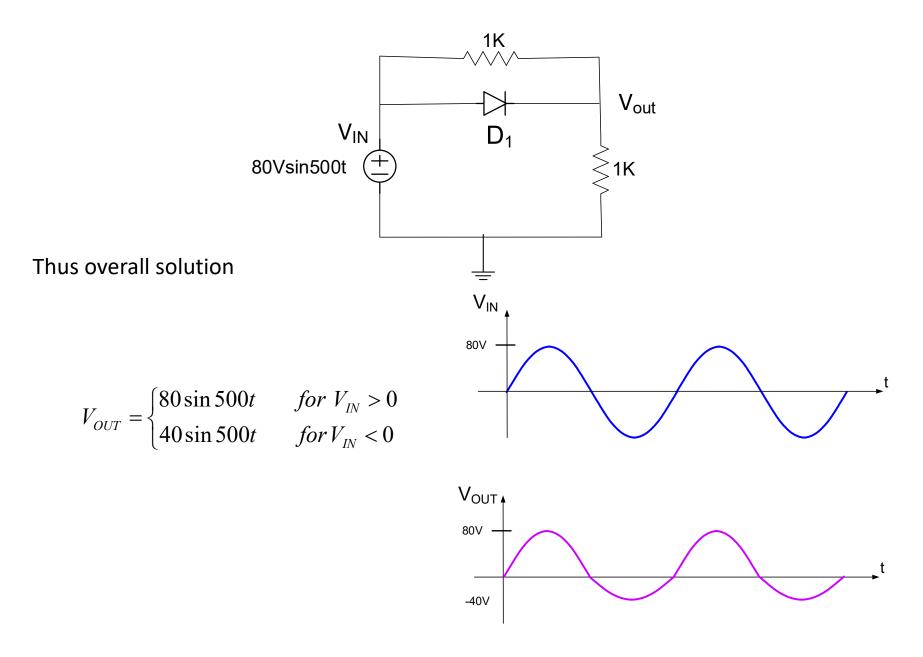
Same process except state verification (step 3) may include a range where solution is valid





Thus valid for $V_{IN} < 0$

Example: Determine V_{OUT} for V_{IN} =80sin500t

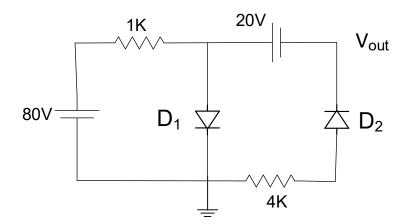


Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

Process:

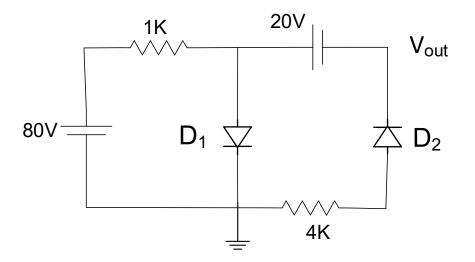
- 1. Guess state of the device
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify model (if necessary)

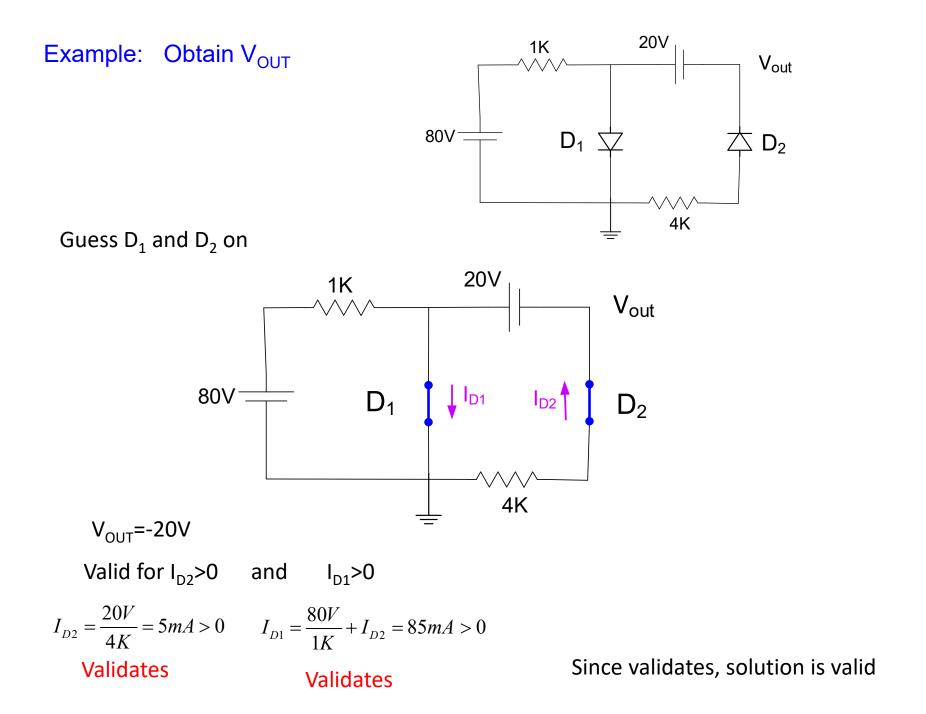
What about circuits (using piecewise models) with multiple nonlinear devices?

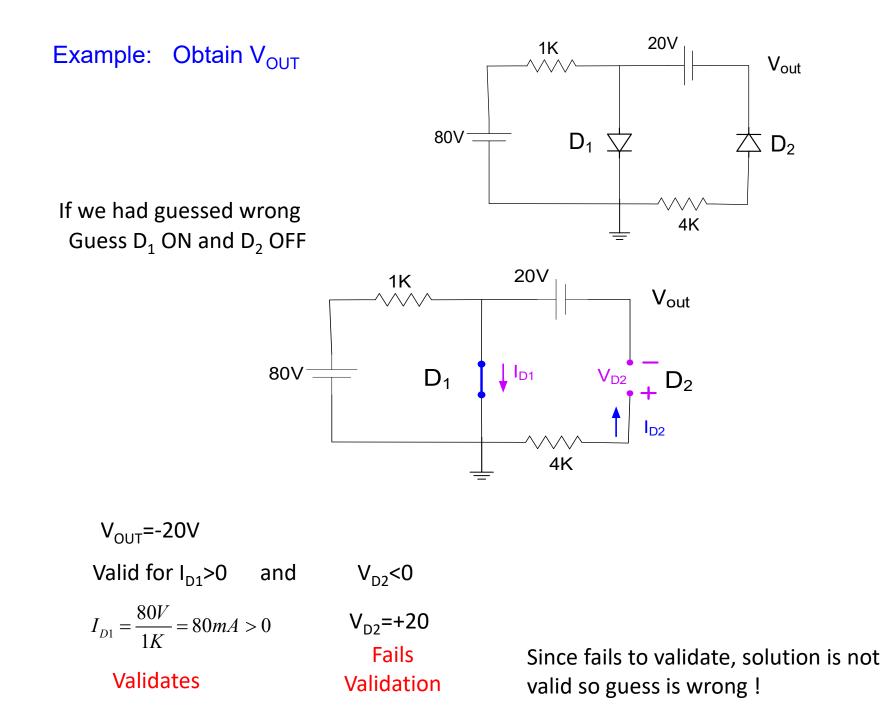


Guess state for each device (multiple combinations possible)

Example: Obtain V_{OUT}







Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

Single Nonlinear Device

Process:

- 1. Guess state of the device
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify model (if necessary)

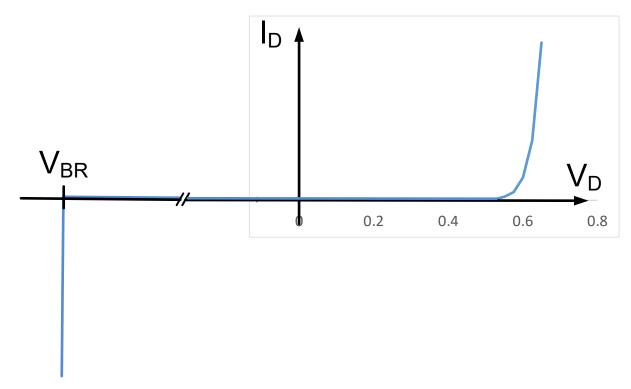
Multiple Nonlinear Devices

Process:

- 1. Guess state of each device (may be multiple combinations)
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify models (if necessary)

Analytical solutions of circuits with multiple nonlinear devices are often impossible to obtain if detailed non-piecewise nonlinear models are used

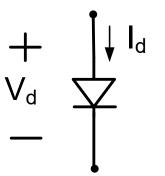
Diode Breakdown

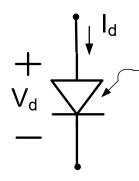


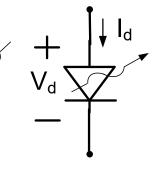
- Diodes will "break down" if a large reverse bias is applied
- Unless current is limited, reverse breakdown is destructive
- Breakdown is very sharp
- For many signal diodes, V_{BR} is in the -100V to -1000V range
- Relatively easy to design circuits so that with correct diodes, breakdown will not occur
- Zener diodes have a relatively small breakdown and current is intentionally limited to use this breakdown to build voltage references

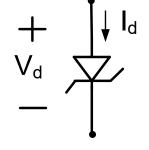
Types of Diodes

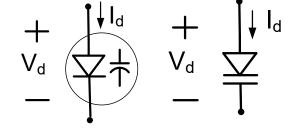
pn junction diodes











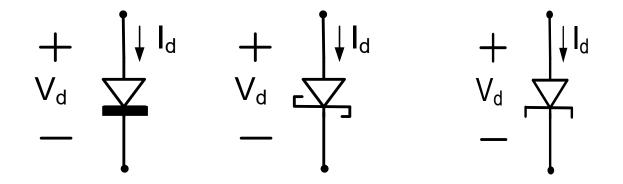
Signal or Rectifier

Pin or Photo Light Emitting LED Laser Diode

Zener

Varactor or Varicap

Metal-semiconductor junction diodes



Schottky Barrier

Basic Devices and Device Models

- Resistor
- Diode

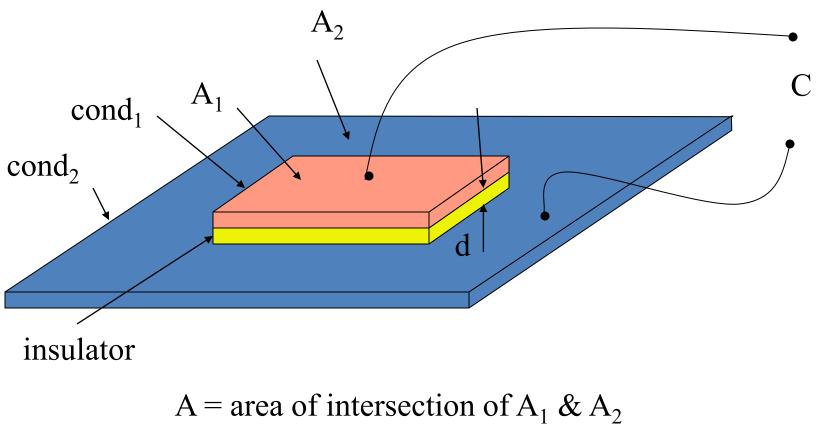


- MOSFET
- BJT

Capacitors

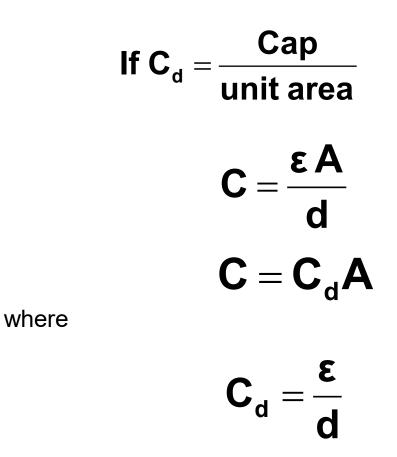
- Types
 - Parallel Plate
 - Fringe
 - Junction

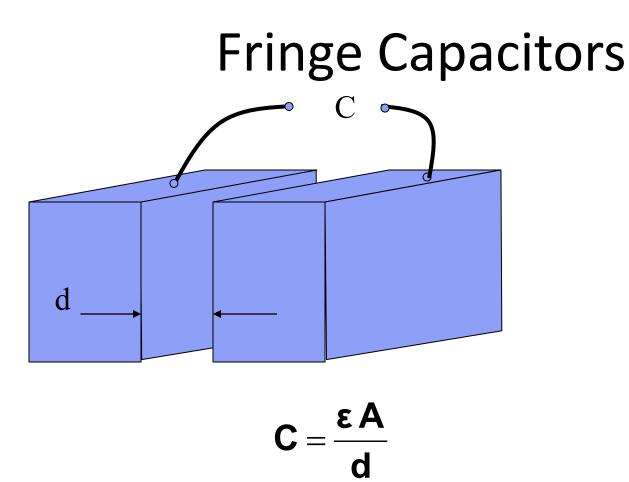
Parallel Plate Capacitors



One (top) plate intentionally sized smaller to determine C $C = \frac{\in A}{d}$

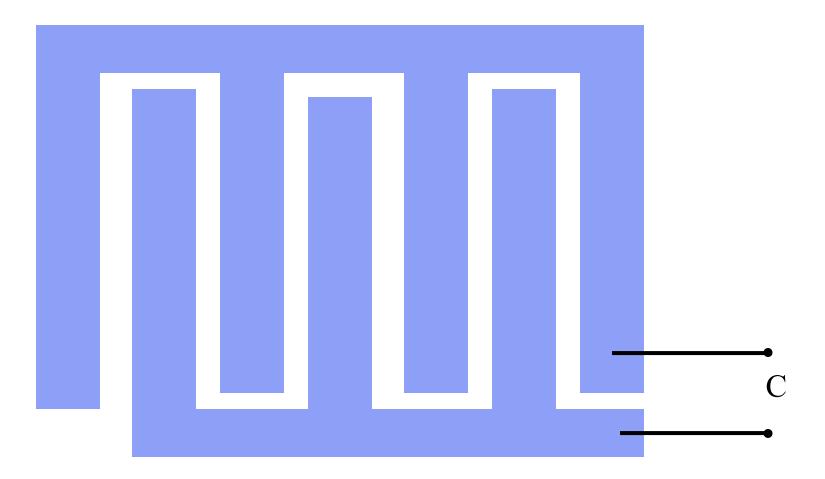
Parallel Plate Capacitors



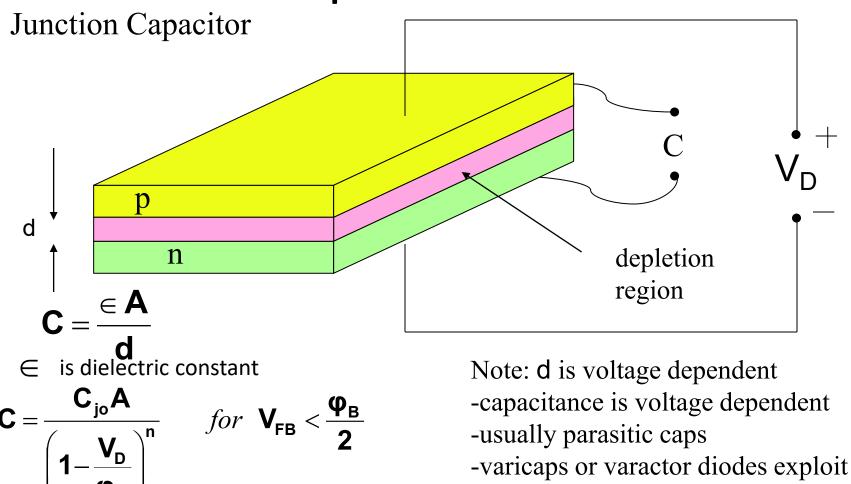


A is the area where the two plates are parallel Only a single layer is needed to make fringe capacitors

Fringe Capacitors



Capacitance

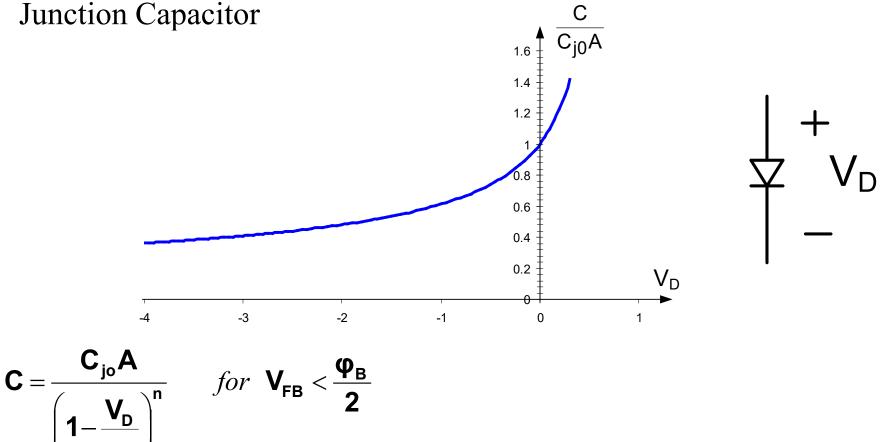


 C_{j0} is the zero—bias junction capacitance density Model parameters { C_{j0} , n, ϕ_B } Design parameters {A}

 $\phi_{\scriptscriptstyle B}\cong 0.6V \qquad n\simeq 0.5 \qquad {\sf C}_{_{jo}} \text{ highly process dependent around 500aF/} \mu\text{m}^2$

voltage dep. of C

Capacitance



Voltage dependence is substantial

 $\phi_{\scriptscriptstyle B}\,{\simeq}\,0.6V\quad n\,{\simeq}\,0.5$

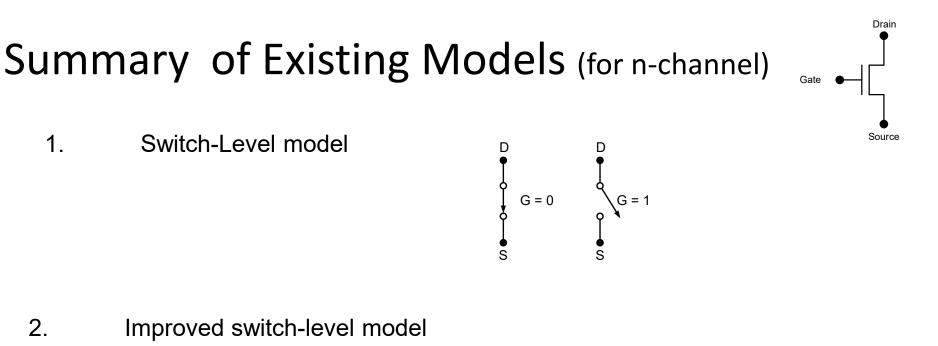
ΨΒ

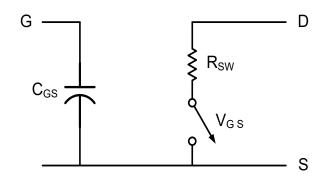
Basic Devices and Device Models

- Resistor
- Diode
- Capacitor



• BJT



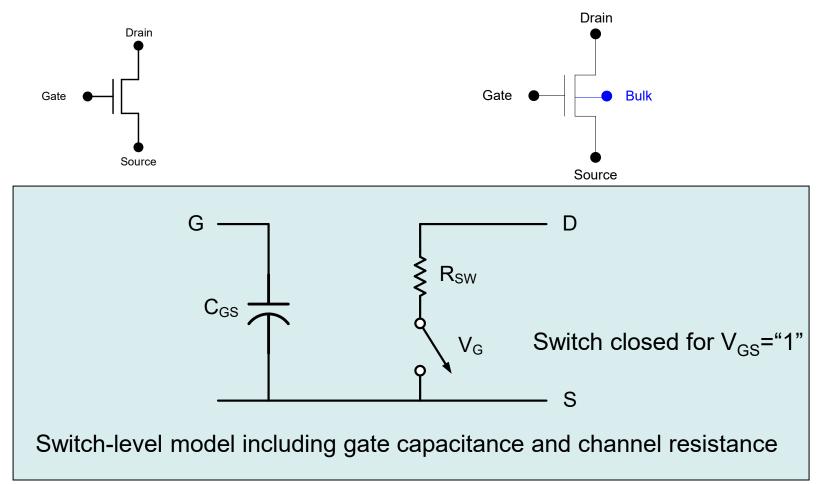


1.

2.

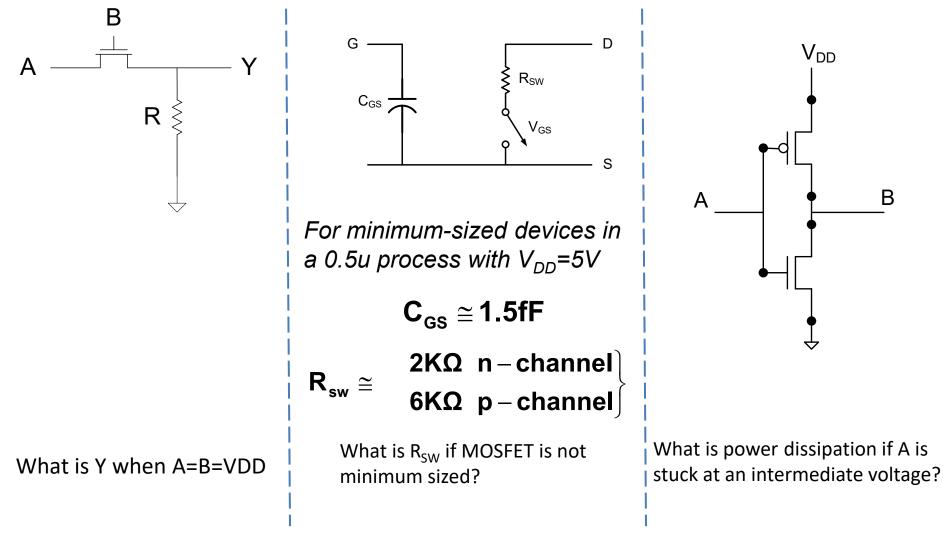
Switch closed for $|V_{GS}|$ = large Switch open for $|V_{GS}|$ = small

Improved Switch-Level Model



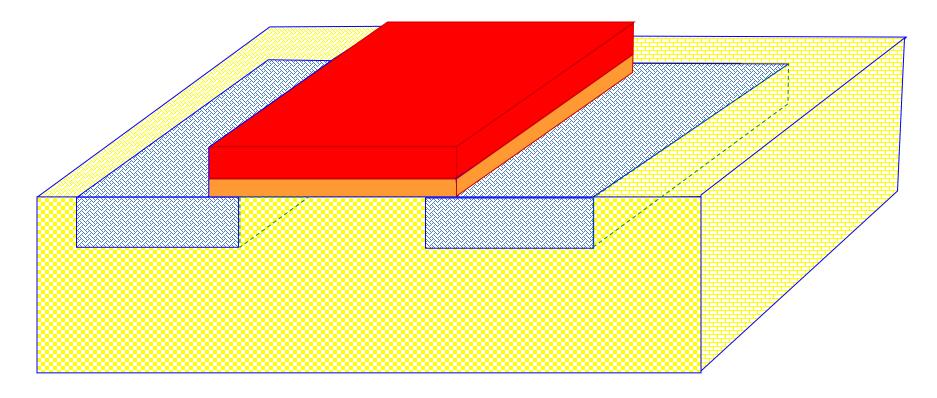
- Connect the gate capacitance to the source to create lumped model
- Still neglect bulk connection

Limitations of Existing MOSFET Models



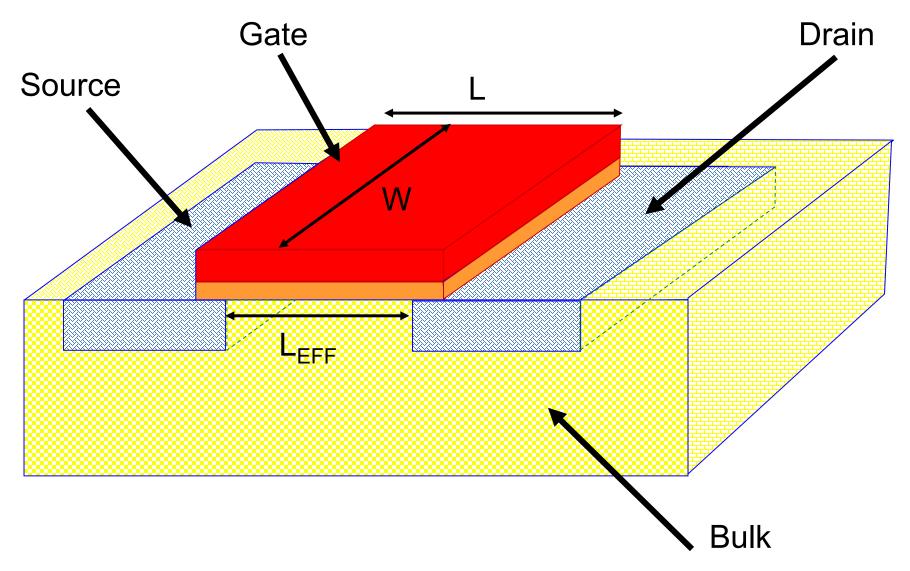
Better Model of MOSFET is Needed!

n-Channel MOSFET

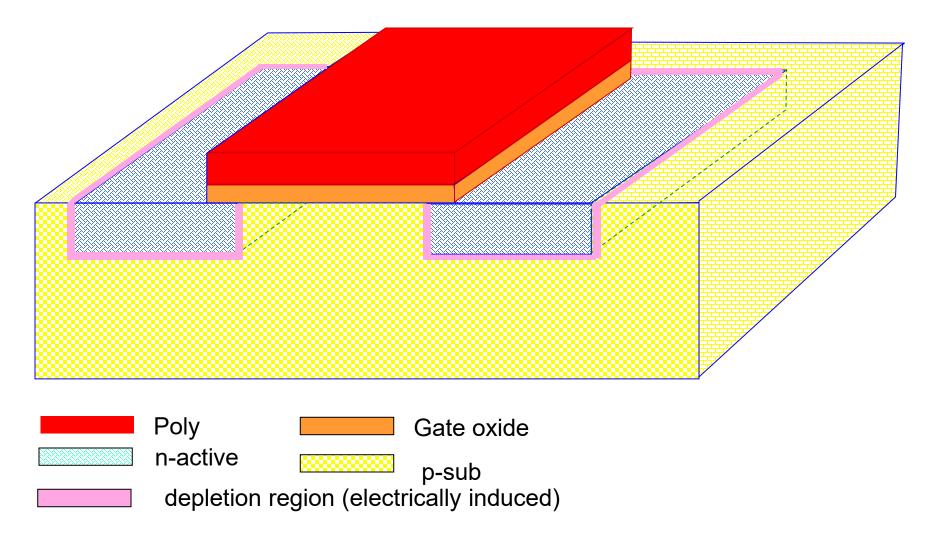




n-Channel MOSFET

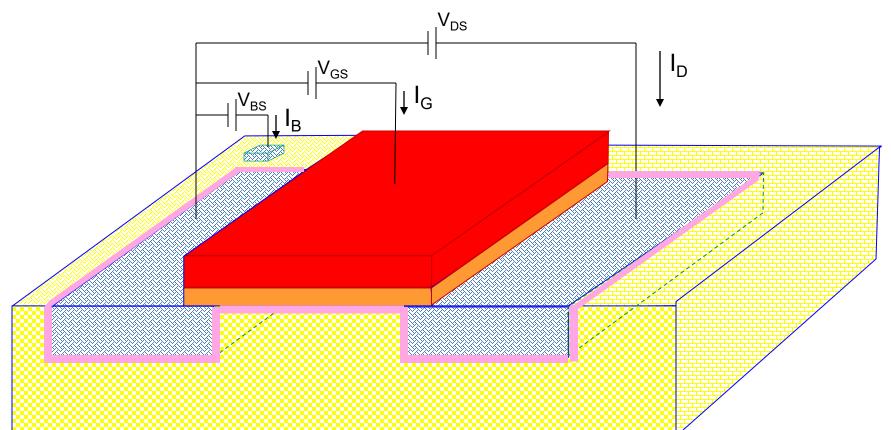


n-Channel MOSFET



- In what follows assume all pn junctions reverse biased (almost always used this way)
- Extremely small reverse bias pn junction current can be neglected in most applications

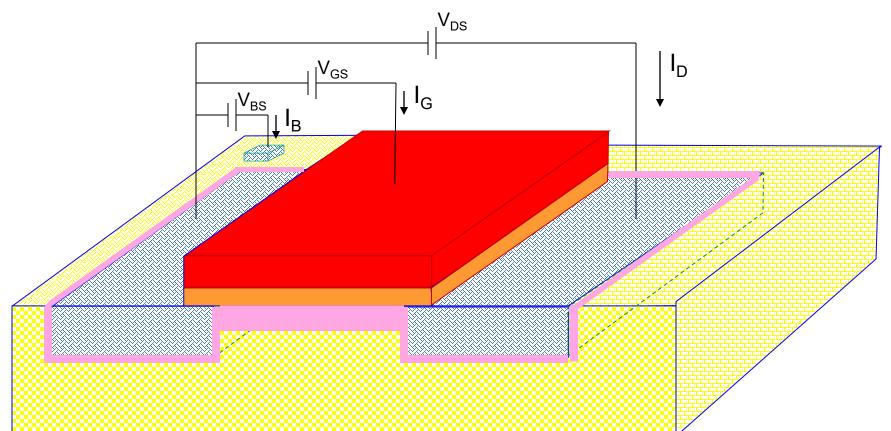
n-Channel MOSFET Operation and Model



Apply small V_{GS} (V_{DS} and V_{BS} assumed to be small) Depletion region electrically induced in channel Termed "cutoff" region of operation

I_D=0 I_G=0 I_B=0

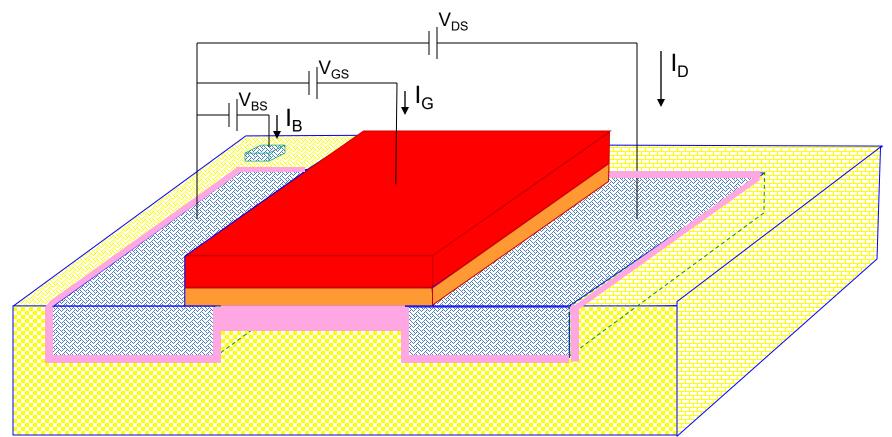
n-Channel MOSFET Operation and Model

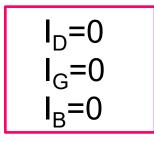


Increase V_{GS} (V_{DS} and V_{BS} assumed to be small)

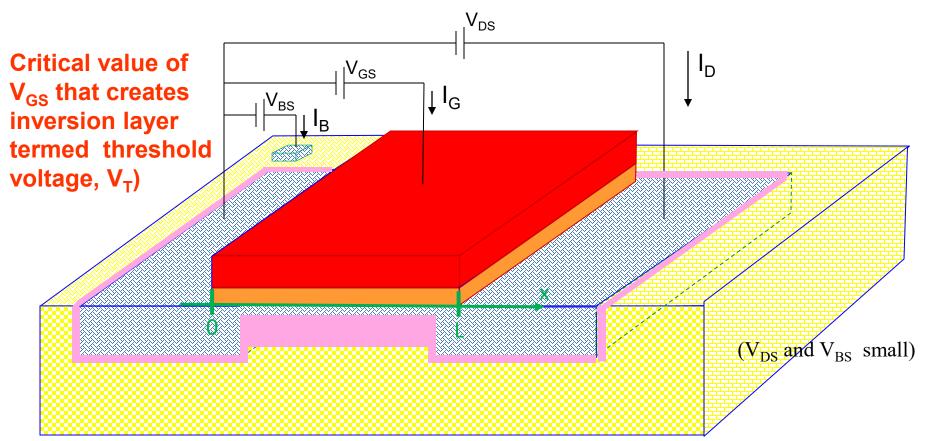
Depletion region in channel becomes larger

I_D=0 I_G=0 I_B=0





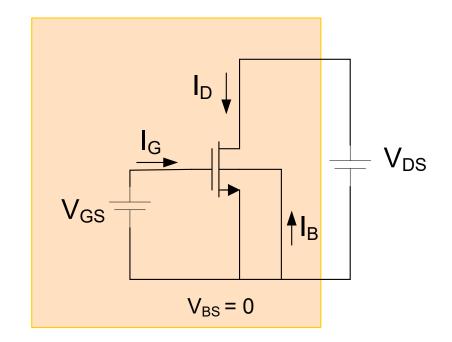
Model in Cutoff Region

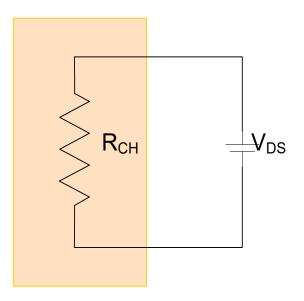


Increase V_{GS} more

Inversion layer forms in channel Inversion layer will support current flow from D to S Channel behaves as thin-film resistor $I_D R_{CH} = V_{DS}$ $I_G = 0$ $I_B = 0$

Triode Region of Operation





For V_{DS} small

$$R_{CH} = \frac{L}{W} \frac{1}{(V_{GS} - V_{TH}) \mu C_{OX}}$$

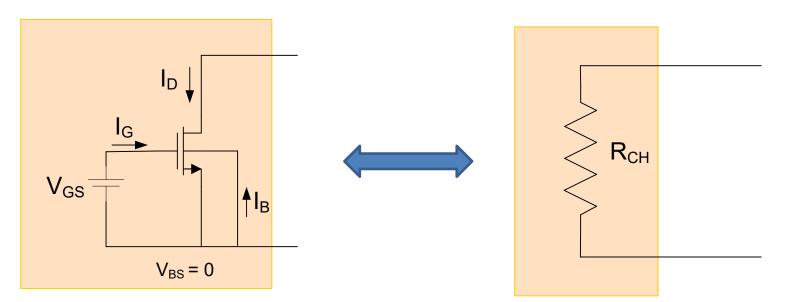
$$I_{D} = \mu C_{OX} \frac{W}{L} (V_{GS} - V_{TH}) V_{DS}$$

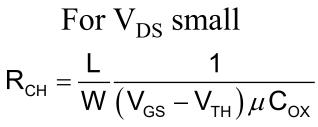
$$I_{G} = I_{B} = 0$$

Behaves as a resistor between drain and source

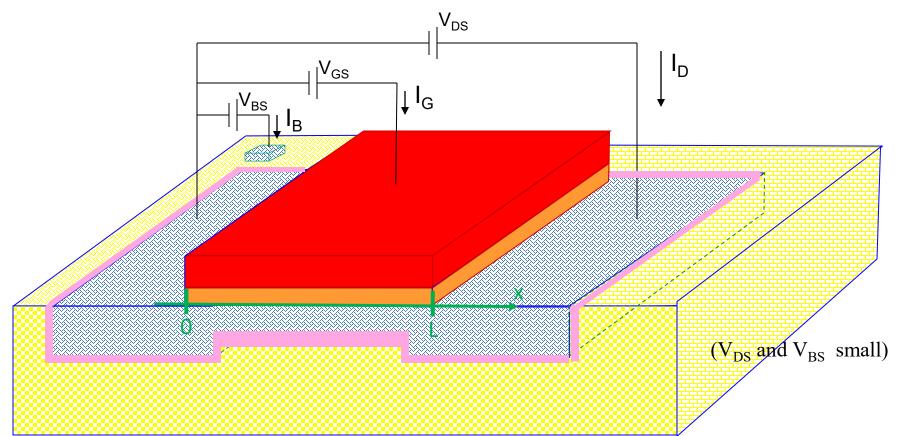
Model in Deep Triode Region

Triode Region of Operation





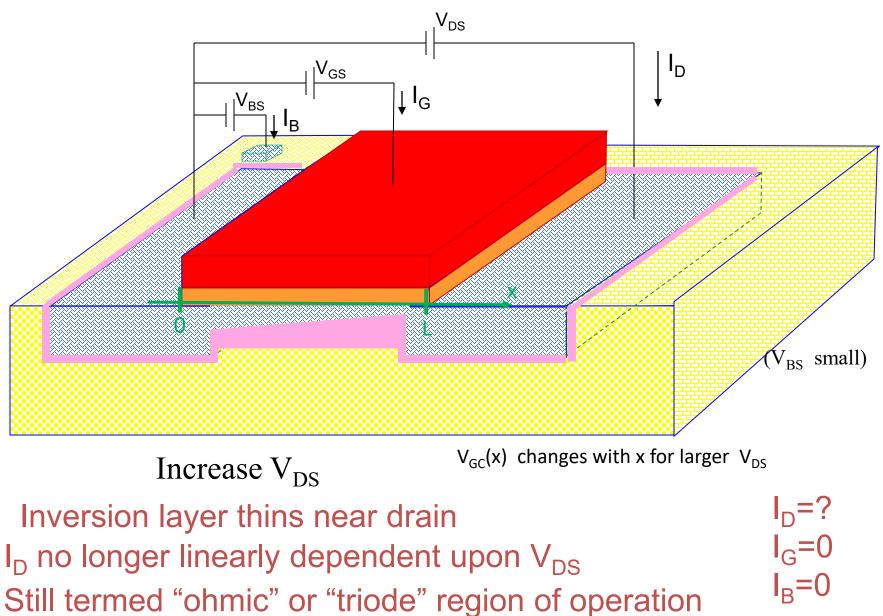
Resistor is controlled by the voltage V_{GS} Termed a "Voltage Controlled Resistor" (VCR)



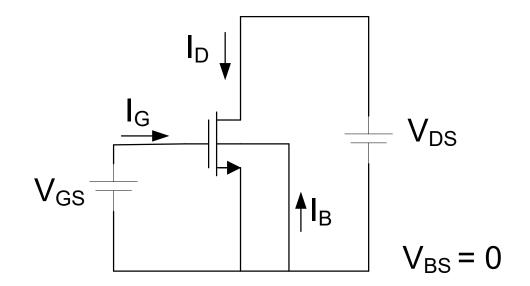
 $V_{GC}(x)$ approx. constant for small V_{DS}

Increase V_{GS} more Inversion layer in channel thickens R_{CH} will decrease Termed "ohmic" or "triode" region of operation

 $I_D R_{CH} = V_{DS}$ $I_G = 0$ $I_B = 0$



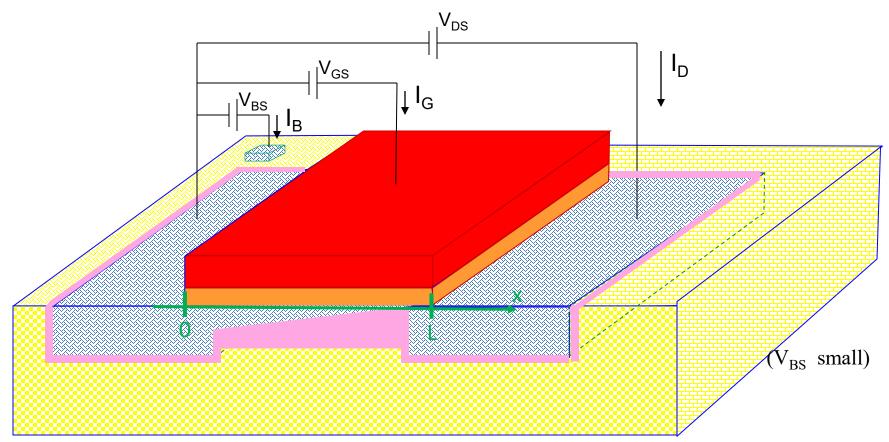
Triode Region of Operation



For V_{DS} larger $R_{CH} = \frac{L}{W} \frac{1}{(V_{GS} - V_{TH}) \mu C_{OX}}$

$$I_{D} = \mu C_{OX} \frac{W}{L} \left(V_{GS} - V_{TH} - \frac{V_{DS}}{2} \right) V_{DS}$$
$$I_{G} = I_{B} = 0$$

Model in Triode Region



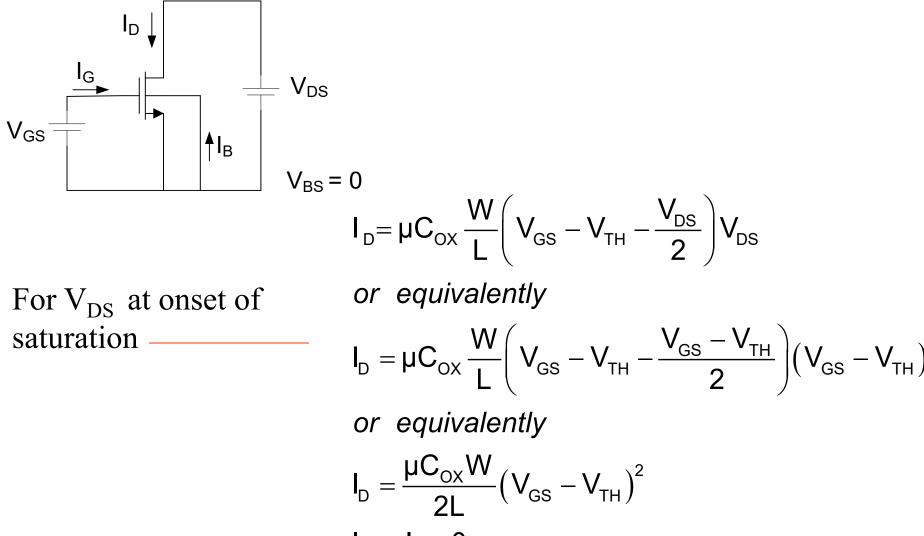
Increase V_{DS} even more

 $V_{GC}(L) = V_{TH}$ when channel saturates

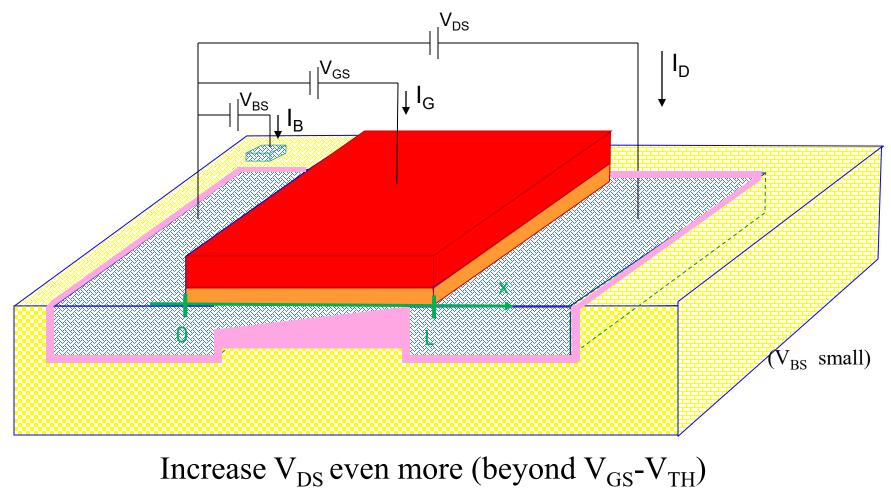
I_D=? I_G=0 I_B=0

Inversion layer disappears near drain Termed "saturation" region of operation Saturation first occurs when $V_{DS}=V_{GS}-V_{TH}$

Saturation Region of Operation



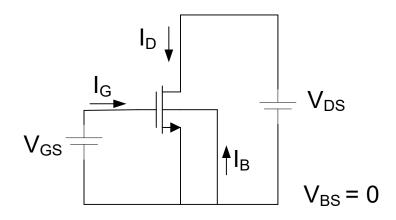
 $I_{\rm G} = I_{\rm B} = 0$



I_D=? I_G=0 I_B=0

Nothing much changes !! Termed "saturation" region of operation

Saturation Region of Operation



For V_{DS} in Saturation

$$I_{D} = \frac{\mu C_{OX} W}{2L} (V_{GS} - V_{TH})^{2}$$
$$I_{G} = I_{B} = 0$$

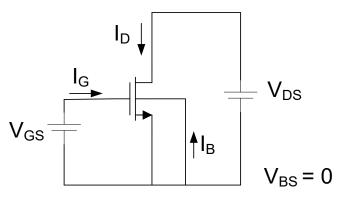
Model in Saturation Region

Model Summary

n-channel MOSFET

Notation change: $V_T = V_{TH}$, don't confuse V_T with $V_t = kT/q$

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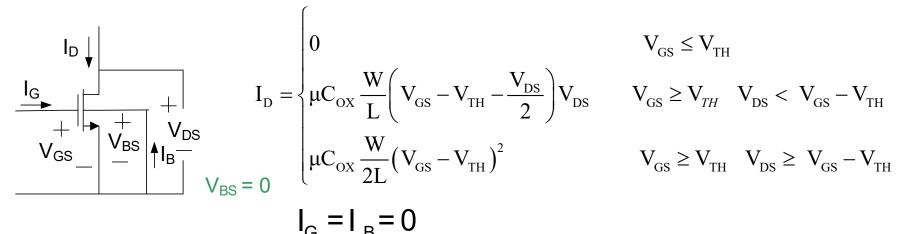
$$I_{D} = \begin{cases} 0 & V_{GS} \leq V_{TH} & \text{Cutoff} \\ \mu C_{OX} \frac{W}{L} \left(V_{GS} - V_{TH} - \frac{V_{DS}}{2} \right) V_{DS} & V_{GS} \geq V_{TH} & V_{DS} < V_{GS} - V_{TH} & \text{Triode} \\ \mu C_{OX} \frac{W}{2L} \left(V_{GS} - V_{TH} \right)^{2} & V_{GS} \geq V_{TH} & V_{DS} \geq V_{GS} - V_{TH} & \text{Saturation} \\ I_{G} = I_{B} = 0 \end{cases}$$

Model Parameters: {μ, V_{TH}, C_{OX}} Design Parameters : {W, L} This is a piecewise model (not piecewise linear though) Piecewise model is continuous at transition between regions

(Deep triode special case of triode where V_{DS} is small $R_{CH} = \frac{L}{W} \frac{1}{(V_{GS} - V_{TH}) \mu C_{OX}}$) Note: This is the third model we have introduced for the MOSFET

Model Summary

n-channel MOSFET

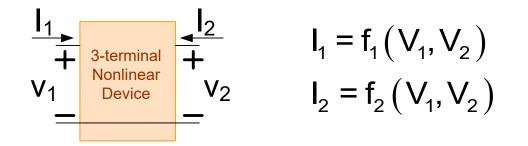


Observations about this model (developed for V_{BS}=0):

 $I_{D} = f_{1} (V_{GS}, V_{DS})$ $I_{G} = f_{2} (V_{GS}, V_{DS})$ $I_{B} = f_{3} (V_{GS}, V_{DS})$

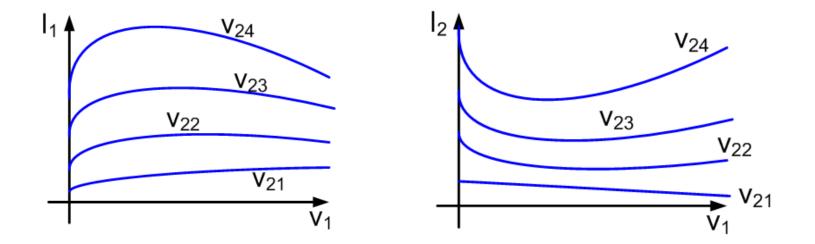
This is a nonlinear model characterized by the functions f_1 , f_2 , and f_3 where we have assumed that the port voltages V_{GS} and V_{DS} are the independent variables and the drain currents are the dependent variables

General Nonlinear Models

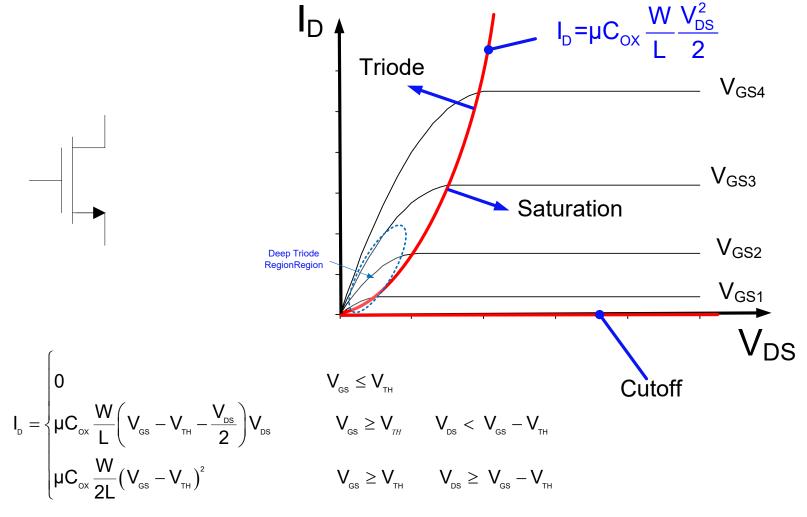


 I_1 and I_2 are 3-dimensional relationships which are often difficult to visualize

Two-dimensional representation of 3-dimensional relationships



Graphical Representation of MOS Model



 $I_{G} = I_{B} = 0$

Parabola separated triode and saturation regions and corresponds to $V_{DS}=V_{GS}-V_{TH}$



Stay Safe and Stay Healthy !

End of Lecture 16